

ABSTRACT OF THE DISCLOSURE (FIG. 2)

"PROCESS SOLUTION SUPPLYING APPARATUS"

A process solution supplying mechanism for
supplying a process solution to a wafer, comprises a
5 source for containing the process solution, a pipe for
introducing the process solution from the source to the
wafer, a process solution supply driving system for
supplying the process solution from the source to the
wafer, and a process solution supplying/stopping
10 mechanism for carrying out apply and stop of the
process solution, wherein the pipe and the process
solution supply driving system are provided separately
and the process solution supplying/stopping mechanism
is provided to a portion other than the pipe.